

Nanohmics

Proximity Glare Suppression for Astronomical Coronagraphs (NASA SBIR Phase 1)

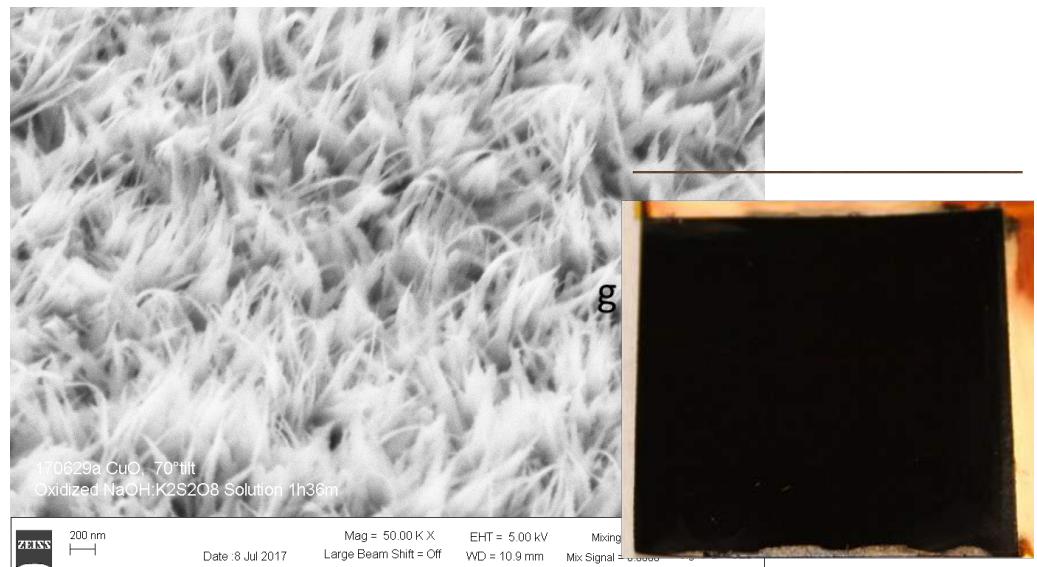
Karun Vijayraghavan, Jesus Meza-Galvan, Jon Diaz, Kieran Lerch, and Byron Zollars

Nanohmics Inc., Austin, TX

kvijay@nanohmics.com

Outline

- Intro to Nanohmics
- High-level vision for proximity glare suppression development
- Anti-reflective surface structures for glare suppression
- FDTD modeling results
- Copper Oxide development and characterization
- Flexible Black Silicon
- Conclusion



About Nanohmics Inc.

**30 Scientists + Engineers
located in Austin, TX**



Electro-optics

- ◆ Surface scattering, BP(R,T)DF
- ◆ System level optical design
- ◆ Optical signal+image processing
- ◆ Infrared emissive devices

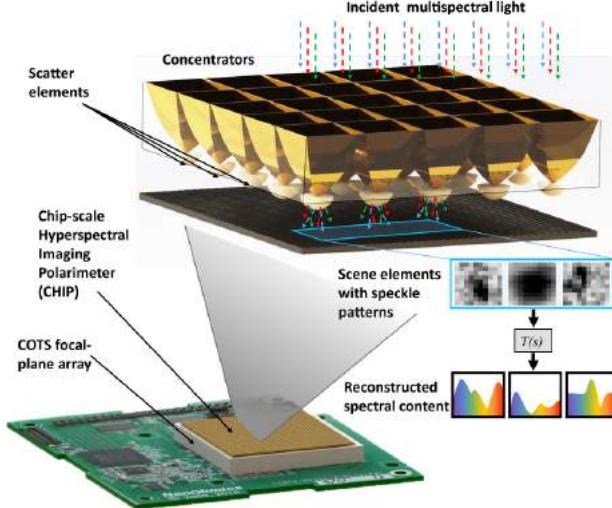
Material Science

- ◆ High-temperature dielectrics
- ◆ Thin-film coating deposition
- ◆ Advanced dielectrics
- ◆ Semiconductor nanostructures

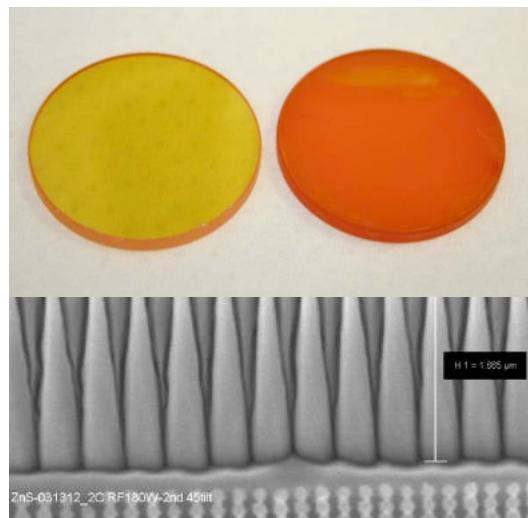
Instrumentation

- ◆ Biological Transduction
- ◆ Low-noise electronics
- ◆ Digital signal/image processing
- ◆ Rapid full-custom prototyping

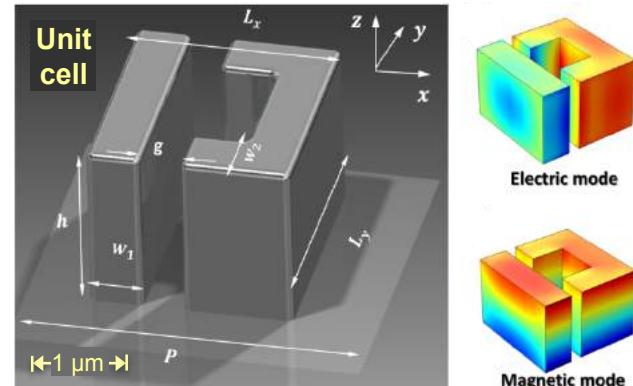
CHIP Hyperspectral Imager



Anti-reflective coatings



Metamaterial optics

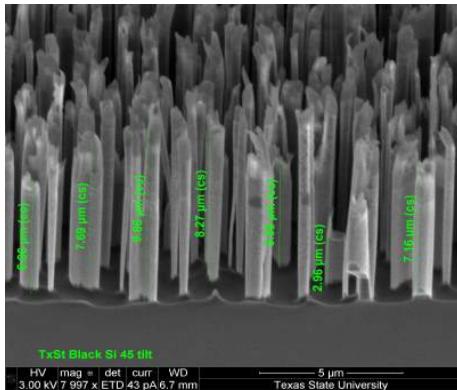


High-level Vision

- Coronagraphs require suppressing starlight to a 10^{-10} contrast level
- Black coatings must be compatible with Flat + Curved surfaces
- Coating materials must be robust against peeling, flaking, outgassing, and cleaning.
- Planar surfaces (i.e. Metal Oxides) have non-negligible specular reflection!

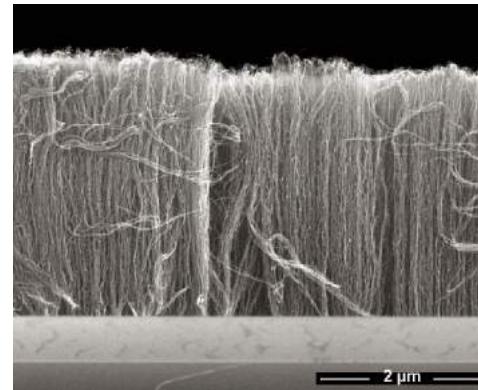
Black Silicon

- <0.5% reflection in Visible + IR spectrum
- Development at JPL
- Fragile to touch
- Flat surfaces only?



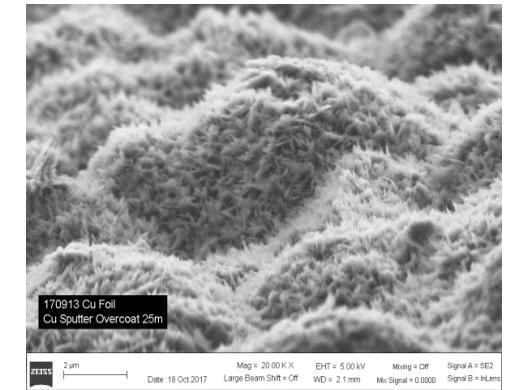
Carbon nanotubes

- 99.5% absorption in visible spectrum
- Development at NASA
- Coat 3D surfaces
- Durability?



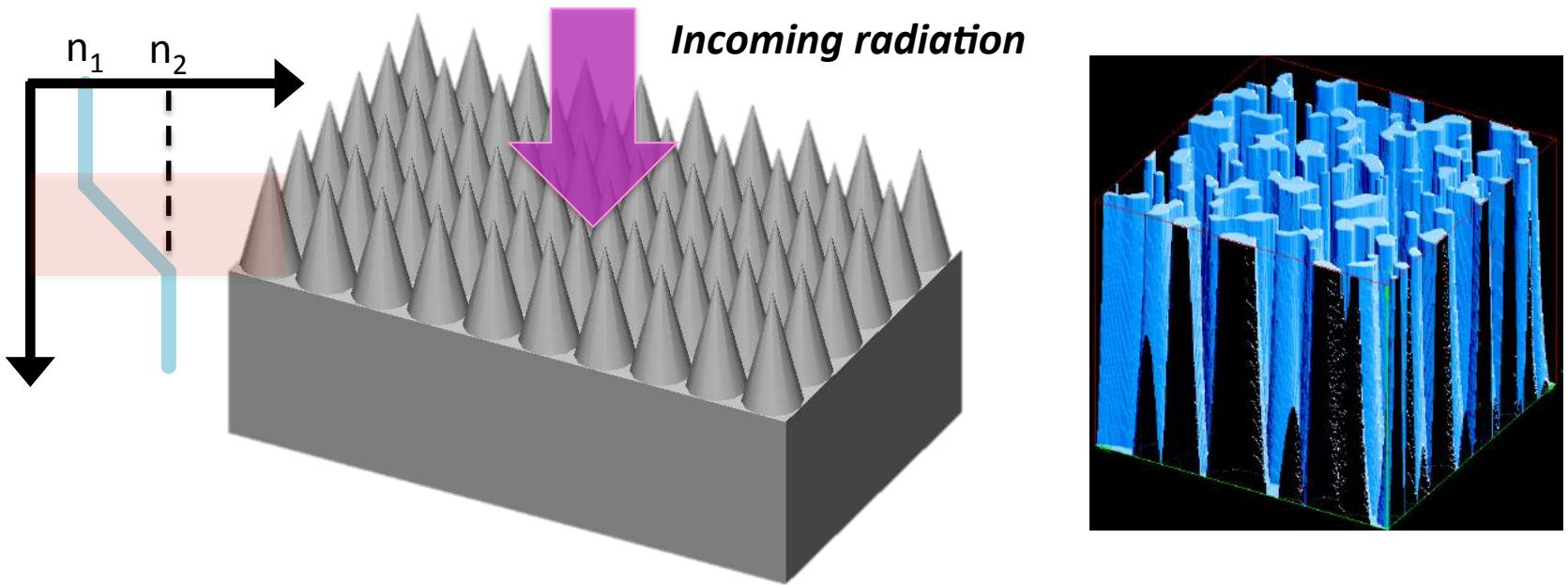
Metal oxides

- Cu, Zn, stainless steel
- Visible + IR spectrum
- Foils, tapes, substrates
- Large area coverage
- Durability?



Develop graded-index anti-reflective structures to suppress reflection from super black absorbing materials over broad angle of incidence/spectrum!

Anti-reflective surface structures (ARSS)

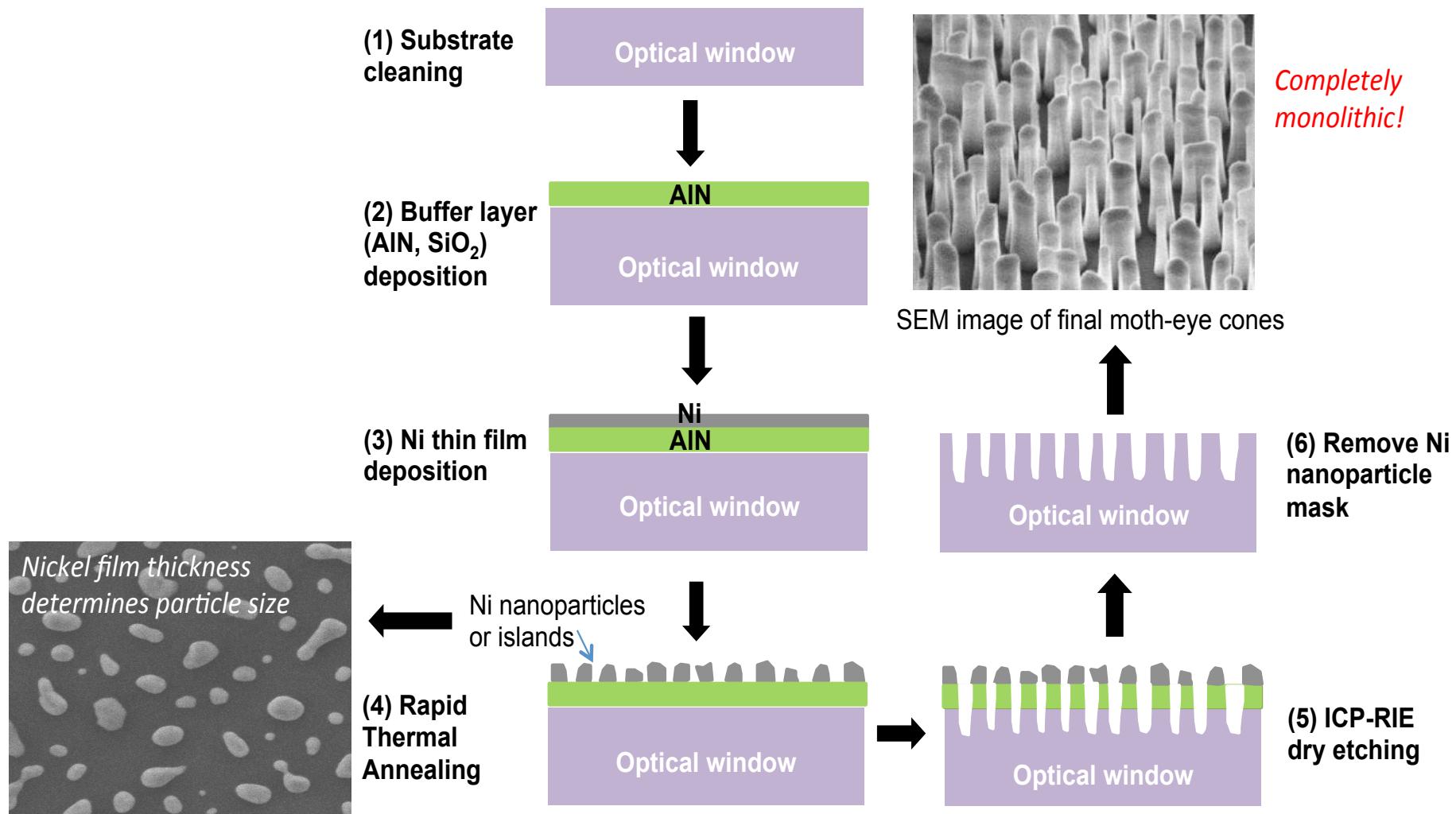


Impedance matching: Graded-index effective medium comprised of sub-wavelength surface structures!

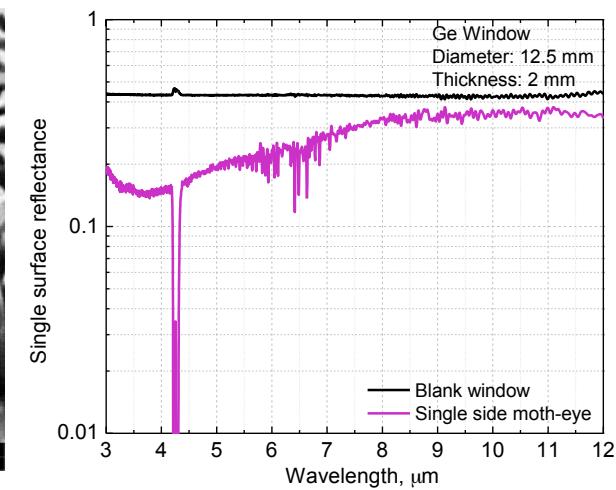
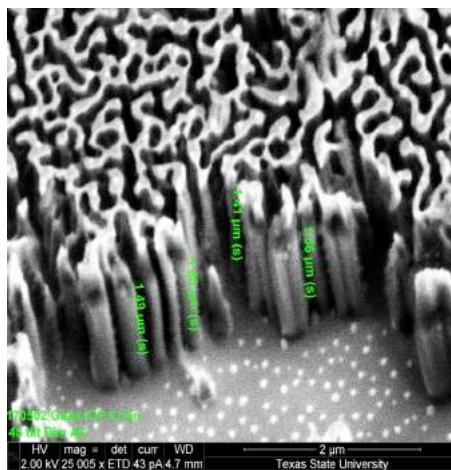
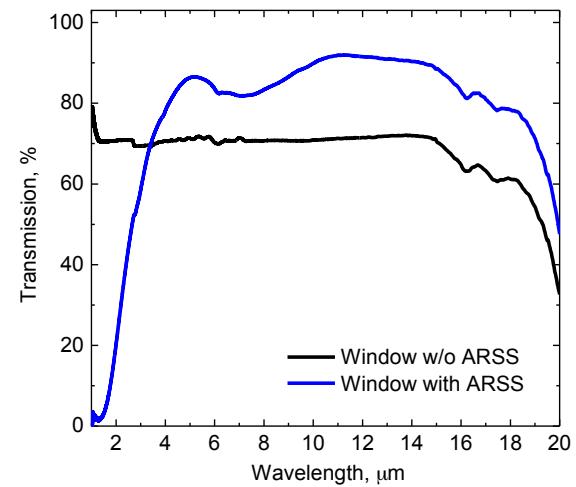
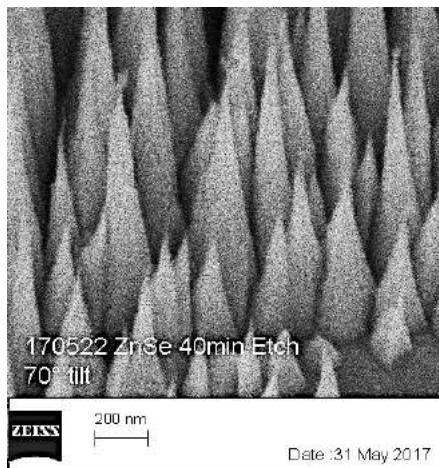
Advantages of anti-reflective surface structure (moth-eye's)

- Broadband anti-reflection performance in the Visible, NIR, SWIR, MWIR and LWIR .
- Anti-reflection performance over 0°-70° of incident angle, for both S and P polarizations
- Ability to be applied to flexible, non-planar substrates, and in well defined areas
- Environmental ruggedness, with nanostructures patterned directly into the substrate
- No chance of delamination, thermal expansion mismatch, or chemical aging
- No flaking, particle formation, or outgassing; Easy cleaning

Thermodot ARSS fabrication process



ARSS-enhanced IR windows and substrates



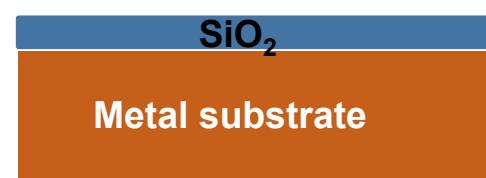
Currently funded by ARMY SBIR Phase 2

Fabrication procedure

(1) Substrate cleaning
(dilute piranha, solvent clean)

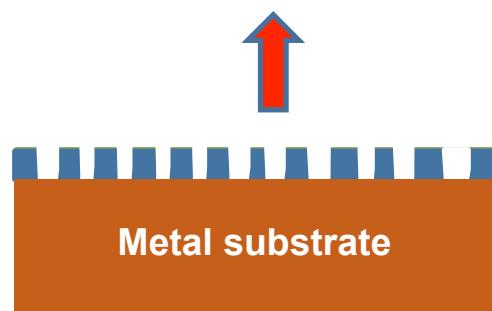
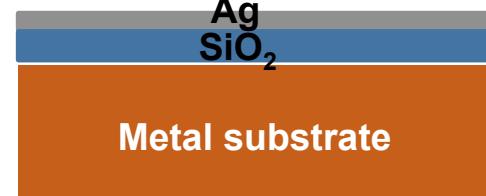


(2) Buffer layer deposition (SiO_2 , 50 – 500 nm thick)



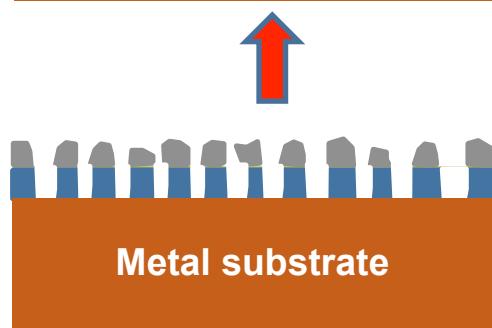
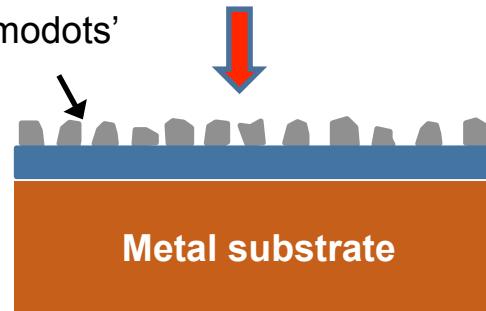
(8) Strip SiO_2 and chemical oxidation

(3) Ag thin film deposition (10–30 nm)



(7) Copper plating

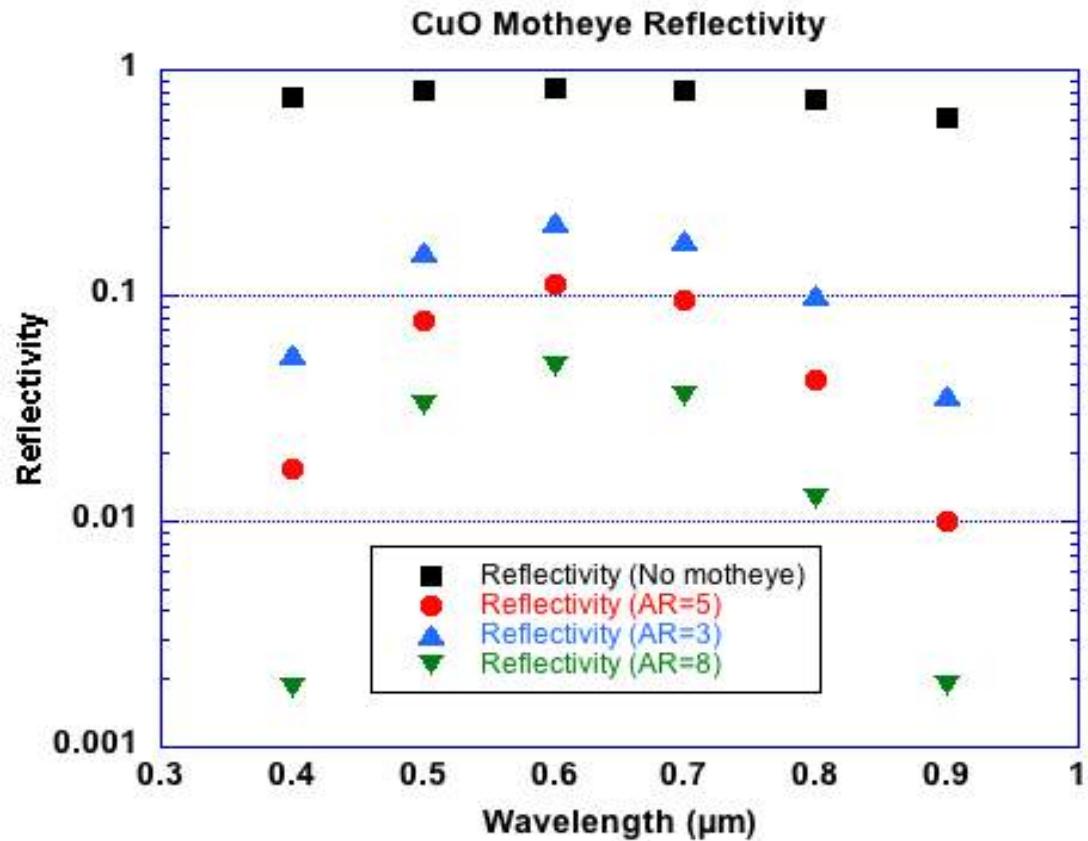
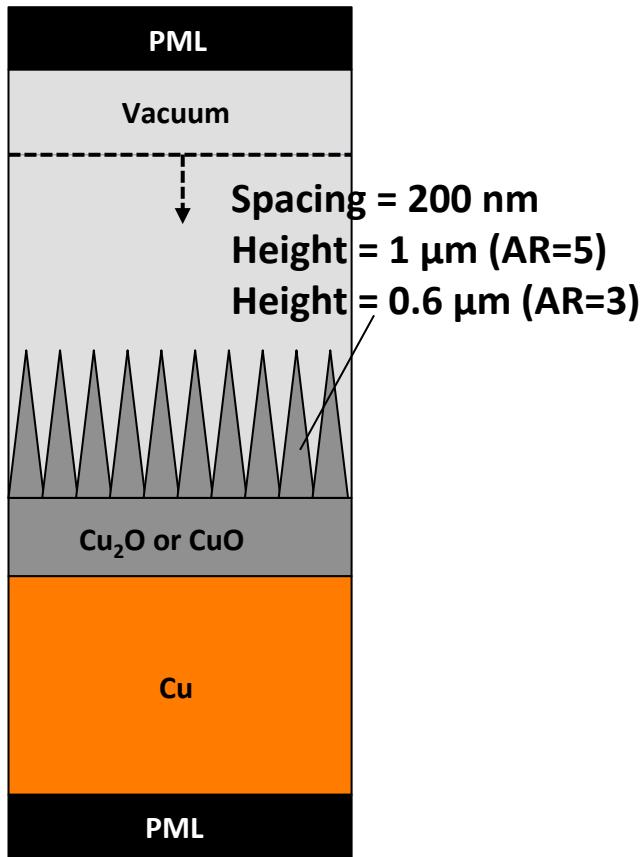
(4) Rapid Thermal Annealing (300–700 °C)



(6) Remove Ag nanoparticle mask

(5) RIE dry etching of SiO_2

Copper oxide ARSS modeling results



- Copper Oxide optical properties taken from literature
- Periodic structure simulated with varying aspect ratios
- Extract size parameters for optimized reflection suppression at a given wavelength

Fabrication and characterization facilities

Nanohmics



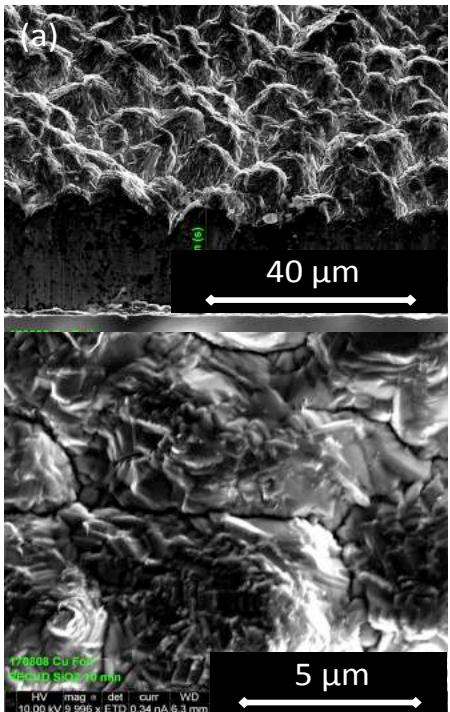
UT Austin - MRC



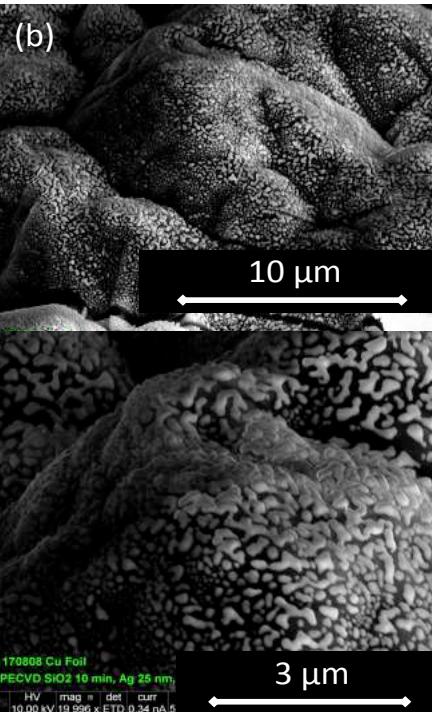
- Class 100/1000 clean room
- Reactive ion etch systems, plasma deposition systems, thermal and electron beam evaporators, scanning electron microscopy, etc.

Fabrication on Copper foils and substrates

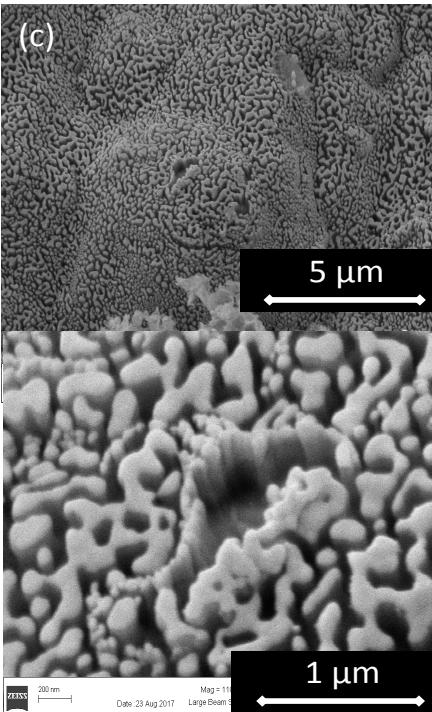
PECVD SiO₂ (500 nm) on Cu foil



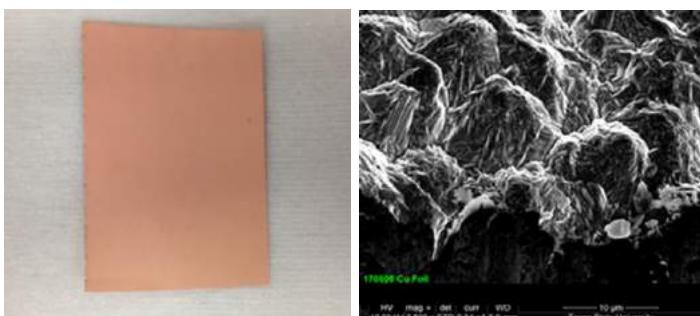
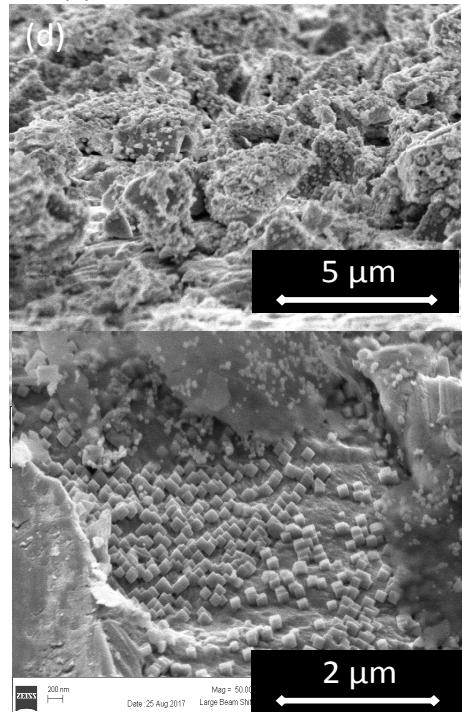
Ag (25 nm) thermodots (500 °C, 120 sec) on SiO₂ on Cu foil



Networked SiO₂ mask on Cu foil



"Networked" electroplated copper on Cu foil



- Successfully fabricated ARSS moth-eyes on Copper foils
- *Copper electroplates completely over the ARSS!*

Copper Oxide on thermodot-patterned Silica

Thermodot

- Ni 10 nm
- RTA 800 °C



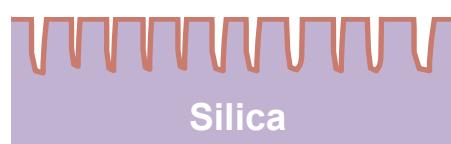
RIE Etch

- $\text{CHF}_3:\text{N}_2:\text{Ar}$
- 80 min - 2 μm



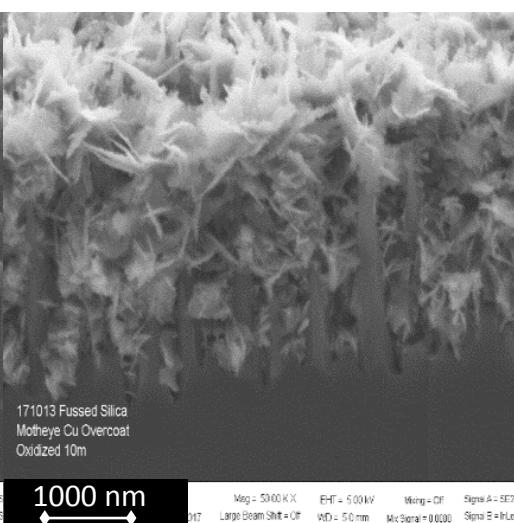
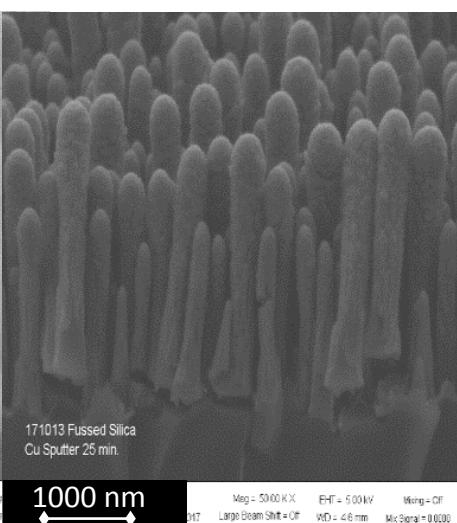
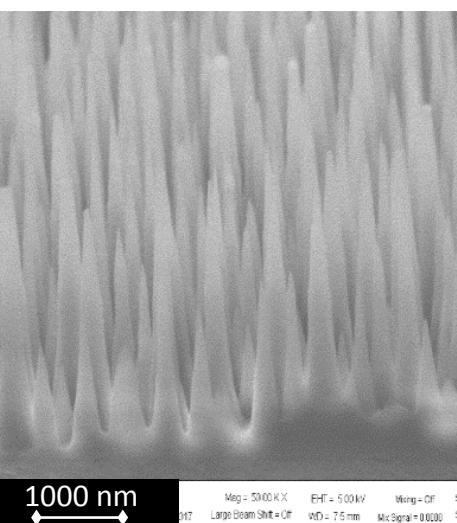
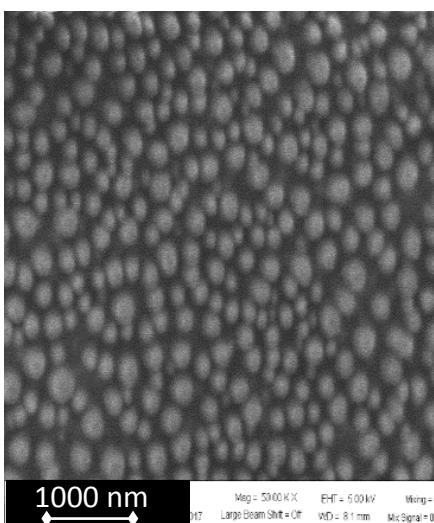
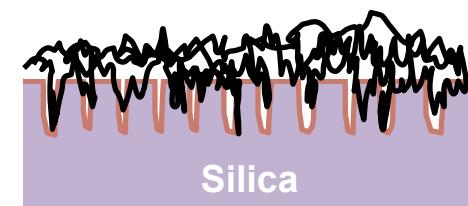
Conformal Coat

- Sputter-deposit 500-nm thick CU



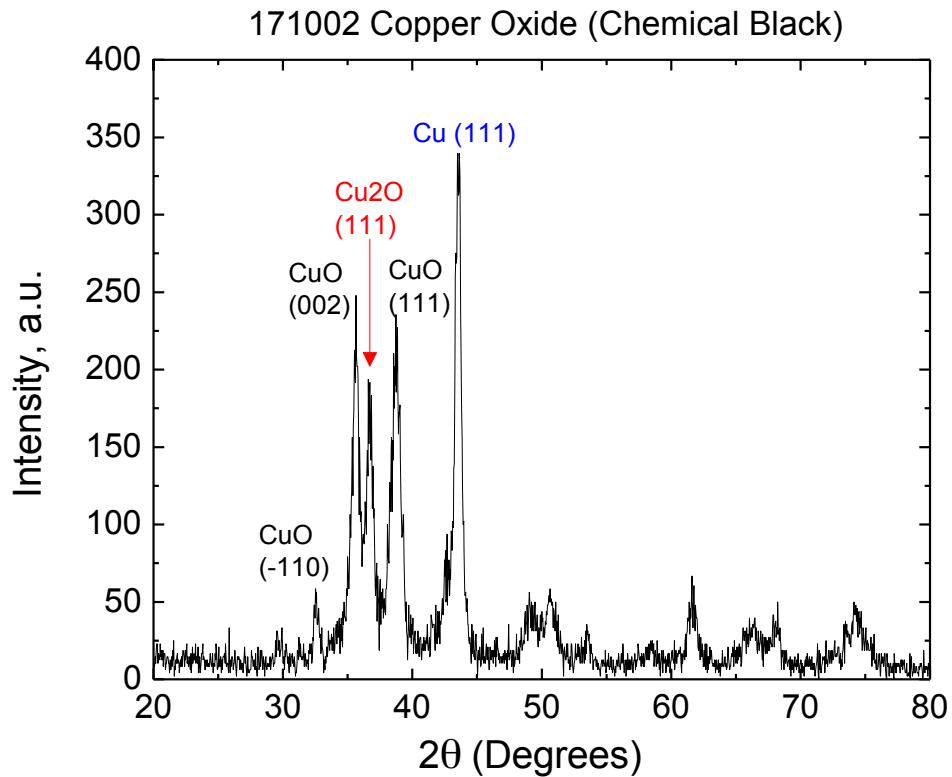
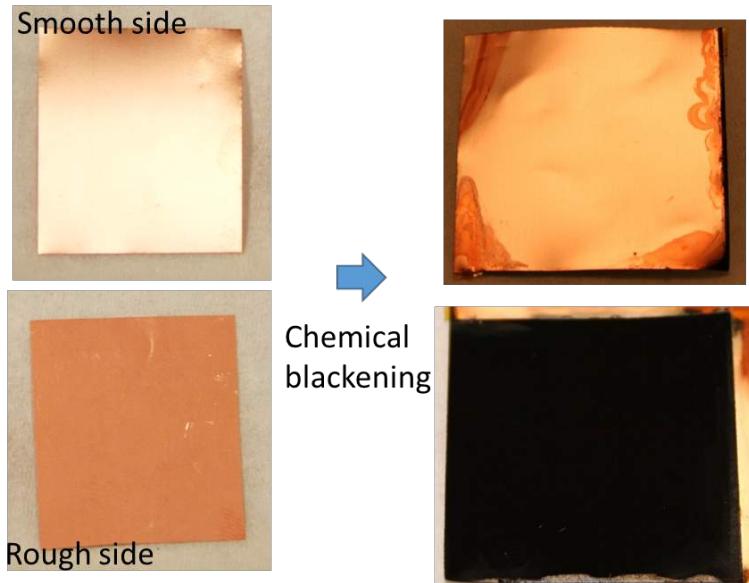
Chemical Oxidation

- $\text{NaOH}:\text{K}_2\text{S}_2\text{O}_8$ bath at 70 °C for 10 min



Chemically synthesized copper oxide is forms over the ARSS moth-eye structures and is naturally textured!

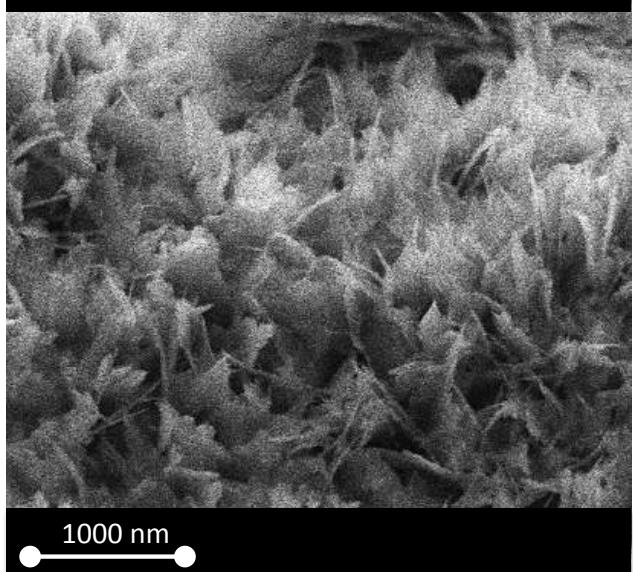
Chemically Black Copper Oxide



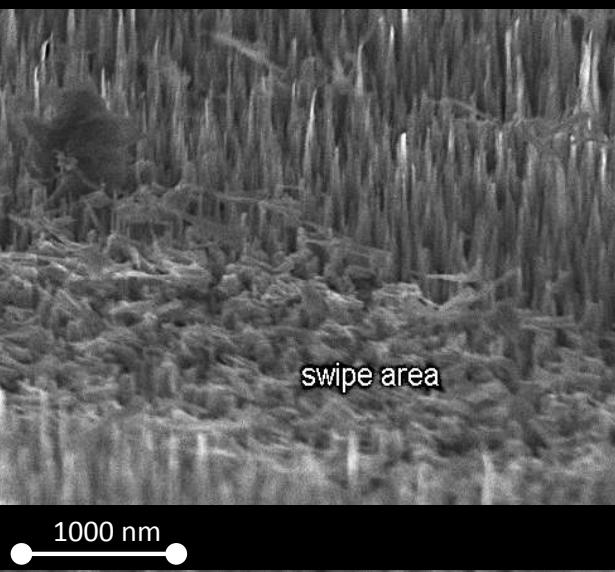
ZEISS 200 nm Mag = 50.00 K X EHT = 5.00 kV Mixing = Off Signal A = SE2
Large Beam Shift = Off WD = 10.9 mm Mix Signal = 0.0000 Signal B = SE2
Date : 8 Jul 2017

Environmental testing

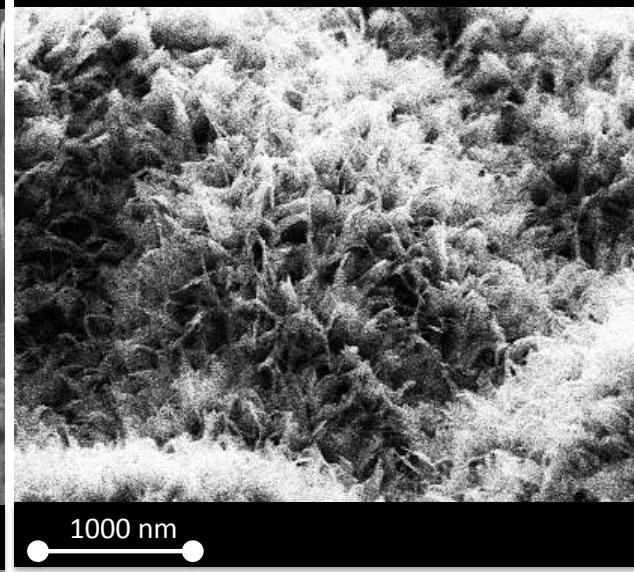
Solvent Clean + Sonication in IPA



Swab test



Temperature Test: 77K – 773 K



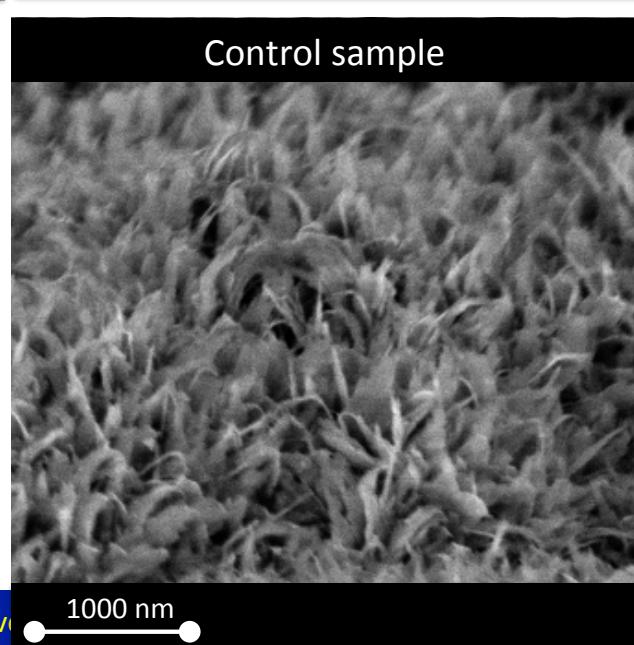
Tolerant against:

- Standard solvent cleans
- Broad operating temperature range (77 – 773 K)
- Outgassing (10^{-8} Torr)
- Bending and folding (flexible foils)

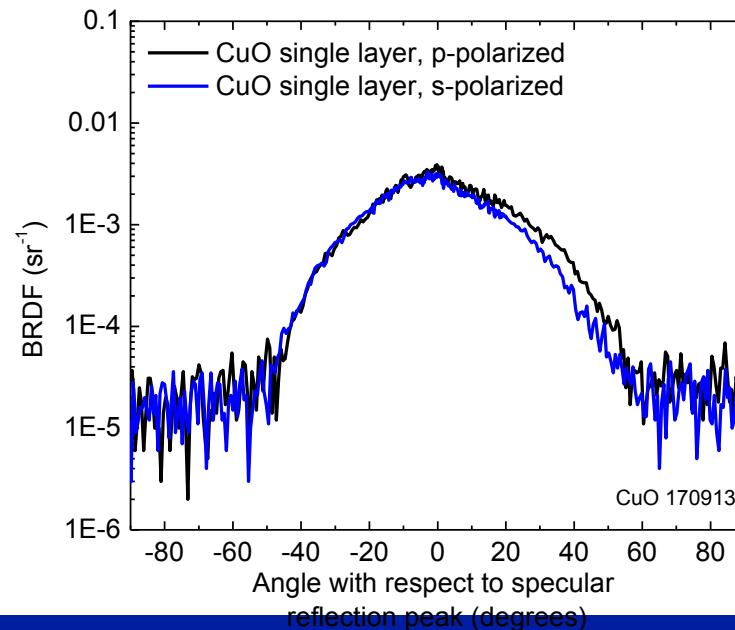
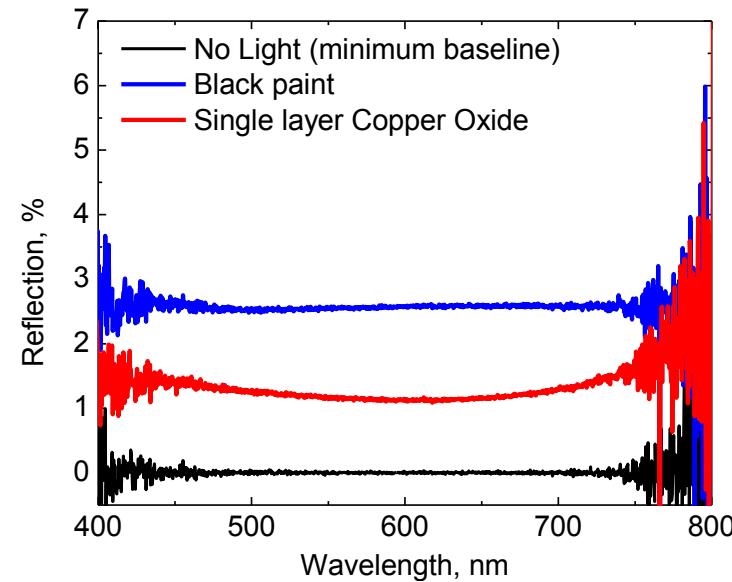
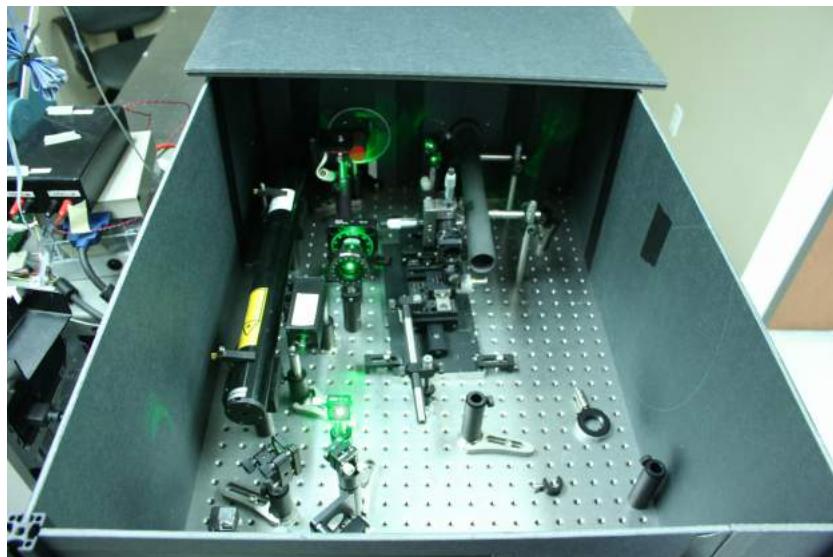
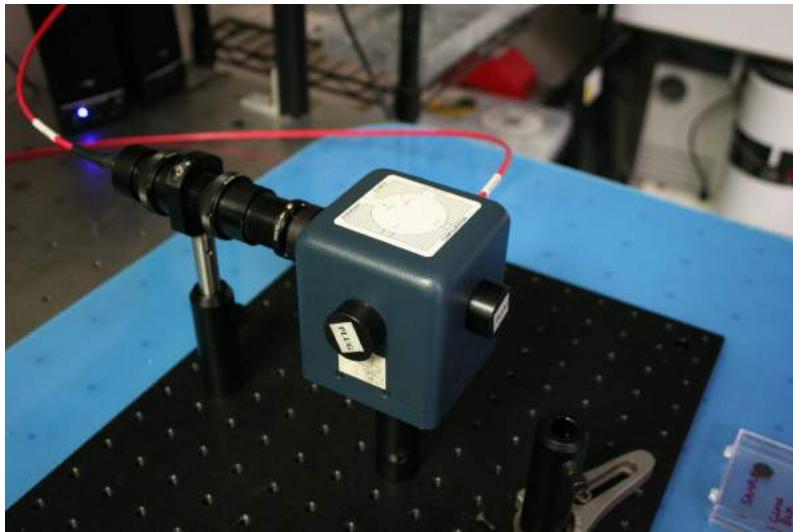
Room for improvement:

- Wiping, swabbing, or touch

Control sample



Preliminary reflectivity characterization



Sputtered Copper Oxide on patterned Silica

Thermodot

- Ni 10 nm
- RTA 800 °C

RIE Etch

- $\text{CHF}_3:\text{N}_2:\text{Ar}$
- 80 min - 2 μm

Conformal Coat

- Sputter-deposit 500-nm thick CuO
- Conformal coating without peeling



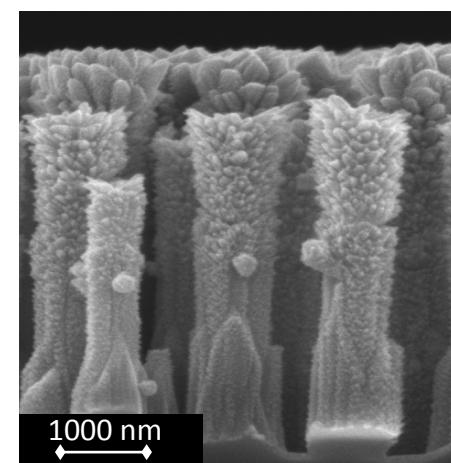
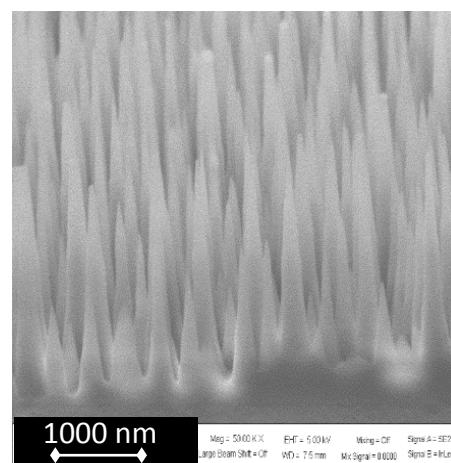
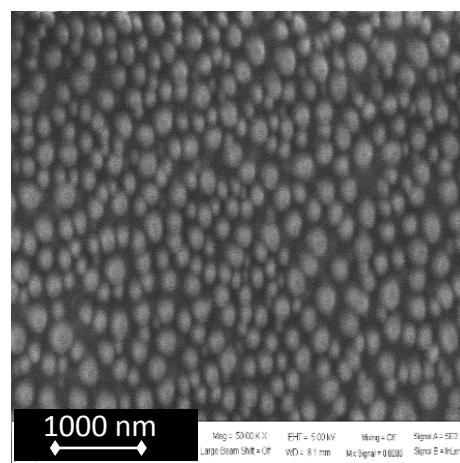
Silica



Silica



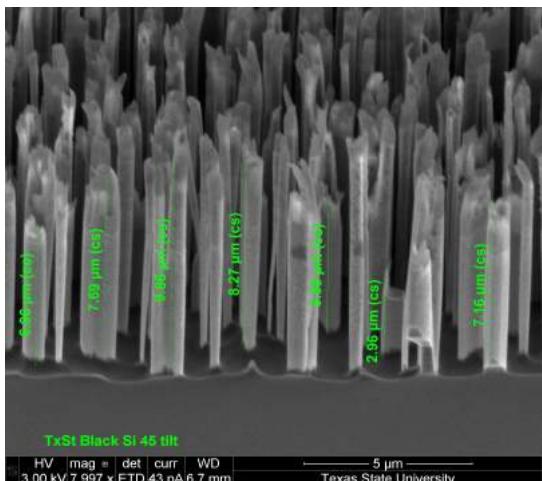
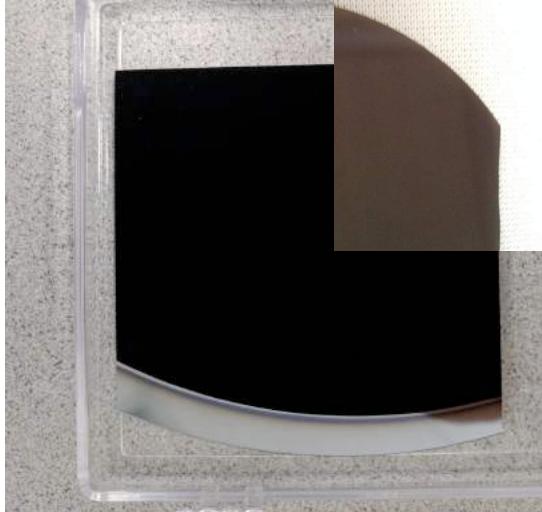
Silica



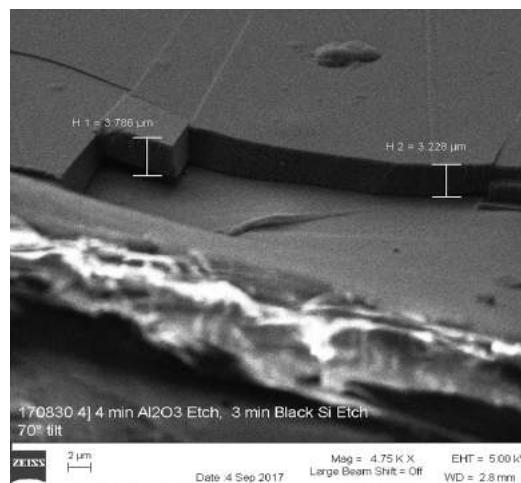
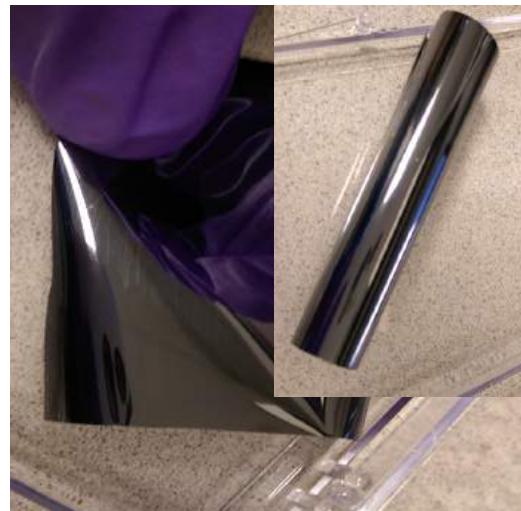
- Form anti-reflective surface structures in a host substrate
- Deposit copper oxide with Argon-assisted magnetron sputtering
- Films have good adhesion and immune to cleaning procedures and processes
- Currently evaluating the spectral performance!

Flexible black silicon

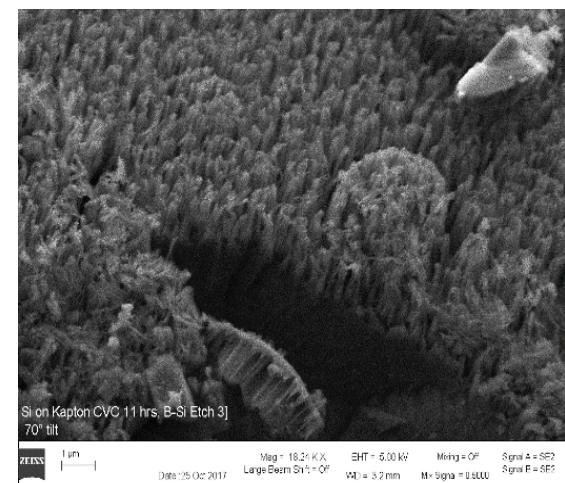
Dry etched Black Silicon on Si wafer



Sputtered Si on Kapton films



Dry etched Black Silicon on Kapton



Summary

- Chemically synthesized CuO on flexible foils and substrates are naturally surface textured.
- Preliminary spectral reflectance ~1% in the visible
- Robust against standard solvent cleaning, heating, cooling and agitation
- Continuing to explore methods of adapting anti-reflective surface structures to CuO
- Currently evaluating sputtered CuO on structures substrates